

目 次

特约专题: 光学传感与成像技术

基于 SPR 的重金属离子检测技术研究进展

..... 刘小锐, 邱娉, 刘倩, 陈嘉杰, 王雪亮, 戴小祺, 黄松锋, 邵永红(1)

扫描式眼波前像差系统的夏克-哈特曼波前传感器质心探测研究

..... 周文豪, 刘佩杰, 尚昆, 曾茜, 郭世俊, 周传清(14)

基于压缩全息散射介质中三维粒子定位 葛洲, 朱靖远, 周文静, 于瀛洁(22)

应用技术

PQ/PMMA 聚合物应用于全息光存储的皱缩特性及影响研究

..... 蒋睿铖, 倪溢棉, 张广威, 陶春先(29)

用于干涉计算成像的硅交叉混频器设计 周文杰, 冯吉军, 于清华(37)

用于大脑疲劳检测的 fNIRS 系统设计 沈无双, 沈慧娟, 苏彤, 王浩, 张学典, 马佩(46)

设计与研究

有机氟离子原位钝化增强 CsPbBr₃ 纳米晶体发光的热稳定性 陈铭彤, 刘灿宇, 游冠军(56)

蓝光 LD 激发 pc-WLED 的发光性能 杨一涵, 黄俐皓, 王鼎成, 李阳, 王轩宇, 隋国荣(64)

矩形阵列磁悬浮热解石墨片光驱转动的研究 黄晓杰, 余明芯, 张大伟, 李建郎(74)

薄 膜

极紫外光刻量产良率的保障: 掩模版保护膜 李笑然, 李丰华(81)

CONTENTS

OPTICAL SENSING AND IMAGING TECHNOLOGY

Research progress on SPR-based heavy metal ion detection technology
···*LIU Xiaorui, QIU Ping, LIU Qian, CHEN Jiajie, WANG Xueliang, DAI Xiaoqi, HUANG Songfeng, SHAO Yonghong* (1)

Centroid detection of Shack-Hartmann wavefront sensor in scanning ocular wavefront aberration measurement system
..... *ZHOU Wenhao, LIU Peijie, SHANG Kun, ZENG Xi, GUO Shijun, ZHOU Chuanqing* (14)

Three-dimensional particle localization in scattering medium based on compressive holography
..... *GE Zhou, ZHU Jingyuan, ZHOU Wenjing, YU Yingjie* (22)

APPLICATION TECHNOLOGY

Study on PQ/PMMA holographic recording characteristics and crumpling
..... *JIANG Ruicheng, NI Yimian, ZHANG Guangwei, TAO Chunxian* (29)

Design of silicon-based cross hybrid for optical interference computation imaging
..... *ZHOU Wenjie, FENG Jijun, YU Qinghua* (37)

Design of fNIRS system used for mental fatigue detection
..... *SHEN Wushuang, SHEN Huijuan, SU Tong, WANG Hao, ZHANG Xuedian, MA Pei* (46)

DESIGN AND RESEARCH

Fluoride ions in situ passivation for thermally stable CsPbBr₃ nanocrystals
..... *CHEN Mingtong, LIU Canyu, YOU Guanjun* (56)

Luminescence performance of pc-WLED excited by blue ray LD
..... *YANG Yihan, HUANG Lihao, WANG Dingcheng, LI Yang, WANG Xuanyu, SUI Guorong* (64)

Optical rotation control of pyrolytic graphite magnetically levitated on square-arrayed magnet
..... *HUANG Xiaojie, YU Mingxin, ZHANG Dawei, LI Jianlang* (74)

FILM

Ensuring the yield of mass production in extreme ultraviolet lithography: the pellicle for mask
..... *LI Xiaoran, LI Fenghua* (81)